# Development of an FET-based NH<sub>3</sub>/NO<sub>x</sub> sensor unit for SCR-control

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### Abstract

This study concerns the tailoring of gas-sensitive FET sensor devices for the development of high-temperature  $NO_x$  and  $NH_3$  sensors applicable for the control of urea-SCR when used as a  $NO_x$  abatement measure in automotive applications through the investigation of the interaction between different series of gas-sensitive materials and  $NH_3$ , NO, and  $NO_2$  at different temperatures.

Key words: FET gas sensors, exhaust emissions monitoring, NH<sub>3</sub> sensing, NO<sub>x</sub> sensing, SCR control

## **Background and motivation**

As it has been concluded that a substantial number of type-approved diesel passenger cars still emit substantially more  $NO_x$  than legally permitted during normal driving, RDE (Real-Drive Emissions) testing has been introduced, whereby in-use vehicles are required to comply with the emissions limits also under real-world driving. To ensure fulfilment of the new regulations, the automotive industry urgently has to adopt much-improved exhaust after-treatment measures for diesel-, and for the future, other lean-burn vehicles than what is most often implemented today.

NO<sub>x</sub> emissions abatement measure generally considered most viable to fulfil the emissions legislation is urea-SCR (Selective Catalytic Reduction). Water-dissolved urea ([NH<sub>2</sub>]<sub>2</sub>CO) is dosed into the exhaust upstream the SCR catalyst, whereby the ammonia (NH<sub>3</sub>) formed in the urea-decomposition reacts with any nitrogen oxides present in the exhaust on the surface of the catalyst. Close control of the urea dosing is necessary, however, since a deficiency of NH<sub>3</sub>, compared to the exhaust NO<sub>x</sub> concentration, will result in NO<sub>x</sub> emissions, whereas excess urea dosing results in the emission of NH<sub>3</sub>, which is one of the substances acting as precursor for formation of ultra-fine particles in the atmosphere. With the emissions legislation and requirements, on-line monitoring of the tailpipeout NO<sub>x</sub> and NH<sub>3</sub> emissions (downstream the catalyst) to fine-tune the urea dosing in a feedback control loop is therefore considered a very attractive solution to achieve the required level of SCR-control. Already today the dosing is based on the  $NO_x$  reading of a  $ZrO_2$  solid electrolyte based sensor upstream the point of urea injection, a sensor which often also is used to monitor the  $NO_x$  concentration downstream the catalyst. Since this sensor also exhibits some sensitivity/ cross-sensitivity to  $NH_3$  and no selective  $NH_3$  sensor to date has been commercialized applicable for on-line exhaust monitoring, the development of a sensor unit able to selectively measure primarily  $NH_3$ , but also  $NO_x$ , with good sensitivity at low concentrations would be of interest.

The SiC-based Field Effect Transistor (FET) sensor platform, see Fig. 1, has previously been shown applicable for in-situ on-line emissions monitoring [1], and an NH3 sensor has also been commercialized from the platform for ammonia slip monitoring in marine applications [2]. As determined by the sensor materials interacting with the exhaust NH<sub>3</sub>, reasonable sensitivity and selectivity can for this existing sensor be found for operating temperatures in the range 275 to 350 °C, which is of less importance in marine applications but not that feasible for NH<sub>3</sub> monitoring in the automotive sector. So far also no FET-based sensor for exhaust NO<sub>x</sub> measurements has been developed. This study was therefore conducted to investigate the possibility of developing and fabricating FET-based sensors for both NH<sub>3</sub> and NO<sub>x</sub> monitoring at the kind of operating temperatures which would enable their use in automotive SCR-control.

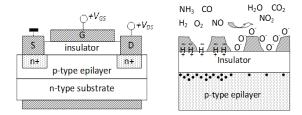
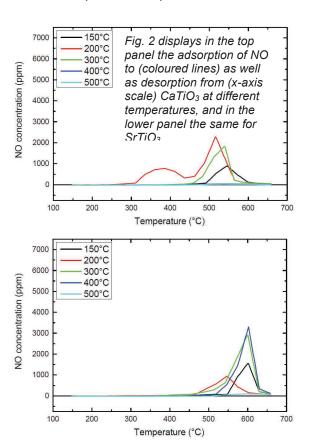


Fig. 1 displays a cross-section of the FET gas sensor device and the mechanism behind its gas-sensitivity

## **Experimental**

The interaction of series of conceptually different materials which can be applied as part of the gate contact in FET devices, such as alkali-earth metals based titanate perovskites and transition metal oxides, with NH3 and NO/ NO<sub>2</sub> at different temperatures were investigated through Temperature Programmed Desorption (TPD) and Mass Spectrometry as well as calorimetry and related to the corresponding observed changes in I/V-characteristics of field effect devices. From the adsorption/ desorption/ reaction interactions investigated at temperatures ranging from 200 to 700 °C, trends in the interaction between NH<sub>3</sub>, NO, and NO<sub>2</sub>, could be established for the series of materials, in relation to operation temperature.



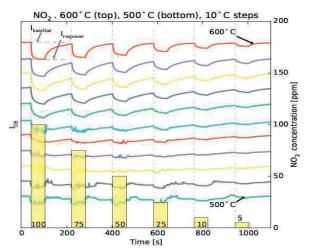


Fig. 3 displays the response of sensors employing  $SrTiO_3$  as part of the gate material at different temperatures, ranging from 500 to 600 °C (bottom to top), to different concentrations of  $NO_x$ .

### Results

An example of the results from the investigation of trends related to adsorption and desorption of NO to a series of Perovskite materials comprising of MgTiO<sub>3</sub>, CaTiO<sub>3</sub>, SrTiO<sub>3</sub>, and BaTiO<sub>3</sub> is given for CaTiO<sub>3</sub> and SrTiO<sub>3</sub> in Fig. 2. As seen from these measurements, dynamic adsorption and desorption of NO occurs at about 600 °C for SrTiO<sub>3</sub>, whereas adsorption and desorption of NO to CaTiO3 occurs over a wider but generally lower range temperatures. Adsorption/ desorption to/ from MgTiO<sub>3</sub> occurs at even lower and for BaTiO<sub>3</sub> at temperatures above 700 °C. As seen from Fig. 3, a good response to NO<sub>x</sub> when employing SrTiO<sub>3</sub> as gas-sensitive material in the FET sensor is achieved for operating temperatures at or slightly below 600 °C. Through the application of NiO as part of the gas-sensitive material, it was also possible to shift the maximum sensitivity towards NH3 to higher operating temperatures than 275-350 °C, in the range of 425-500 °C

# References

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